# IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re application of:

Toshihiko HIGUCHI

Serial No: 09/910,447

Filed:

July 19, 2001

For:

SEMICONDUCTOR DEVICE

HAVING A CONTROLLED GATE SHAPE AND METHOD FOR

MANUFACTURING THE SAME

(Amended)

#### <u>AMENDMENT</u>

Commissioner for Patents Washington, D.C. 20231

Art Unit: 2814

Examiner: Thao X. Le

I hereby certify that this correspondence is being transmitted via facsimile to (703) 872-9318: Commissioner for Patents, Washington D.C. 20231, on

September 5, 2002 Date of Deposit

Diane Zynn

Name Diane Signature

09/08/02

**FAX COPY RECEIVED** 

2002 SEP 5

**TECHNOLOGY CENTER 2800** 

Dear Sir:

In response to the Office Action dated June 5, 2002, please amend the abovereferenced application as follows:

### IN THE TITLE:

Please amend the title to read "Semiconductor Device Having a Controlled Gate Shape and Method for Manufacturing the Same"

### IN THE CLAIMS

Please cancel claim 8 without prejudice.

## Please replace the text of claims 1, 5 and 9-12 with the following text:

- A semiconductor device comprising: 1.
- a semiconductor substrate;

a gate electrode formed on the semiconductor substrate through a gate dielectric layer;

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